

# Electrothermal simulation of large-area semiconductor devices

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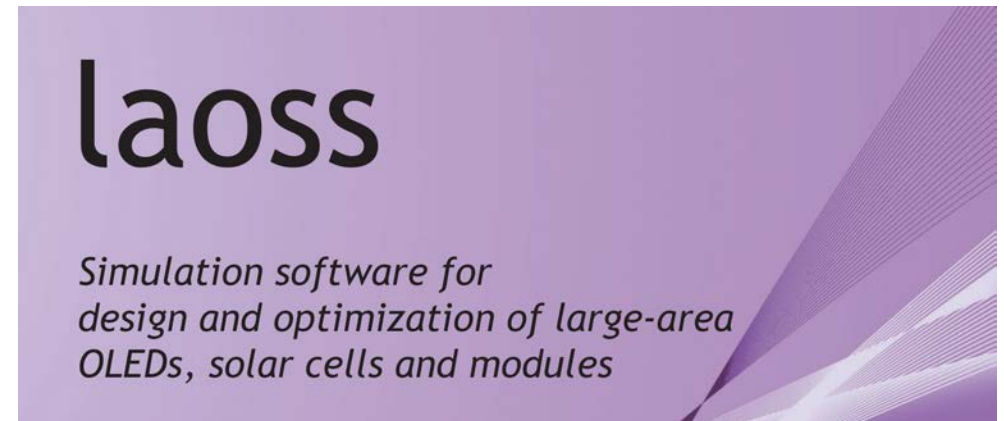
# LAOSS CTI project (2016–2018)

The results presented here were obtained within the

Large Area Organic Semiconductor Software (LAOSS)

project, funded by the Swiss Commission for Technology and Innovation (CTI; now Innosuisse) from 2016–2018.

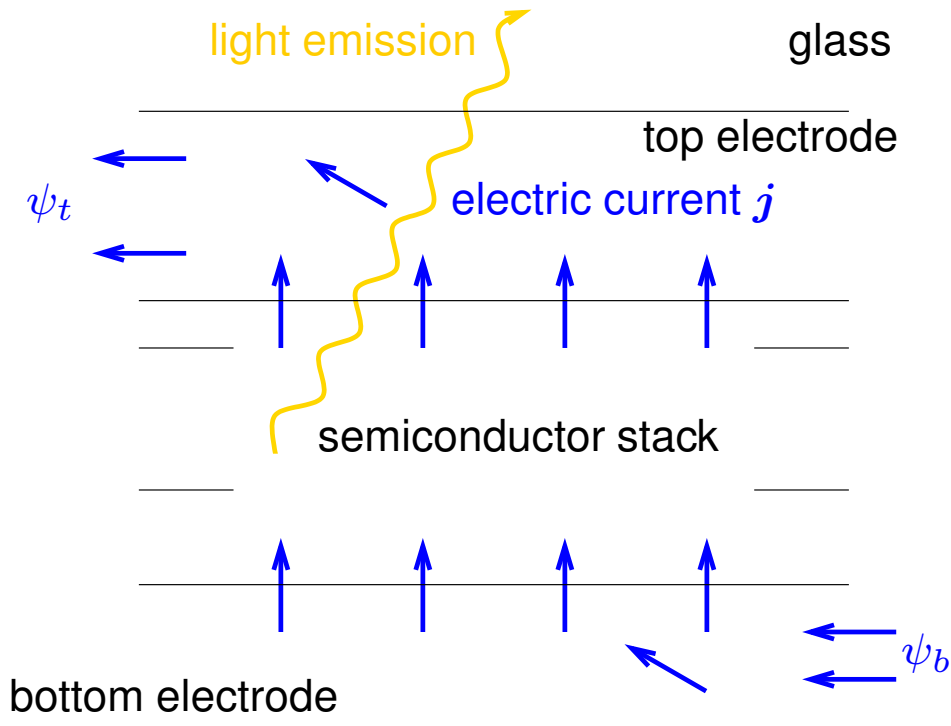
Within this research project a prototype model was developed at the ICP for testing new ideas, some of which went into Fluxim's Laoss software.



A “large-area device” is a device in which the lateral charge transport in the electrodes has a significant effect on the device performance.

# Charge transport and heat transfer

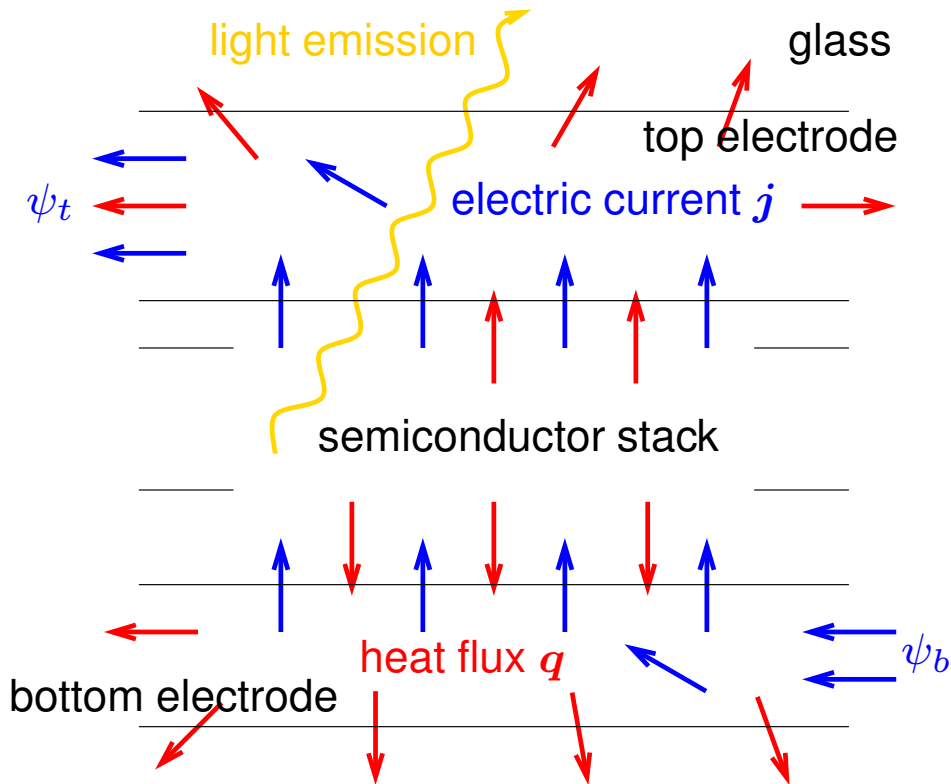
Multilayer semiconductor stack between two electrodes (e. g. OLED):



- **charge transport** governed by Ohm's law:  $j = -\sigma \nabla \psi$  [ $\text{Am}^{-2}$ ]  
electrical conductivity  $\sigma$  [ $\text{Sm}^{-1}$ ]  
electric potential  $\psi$  [V]

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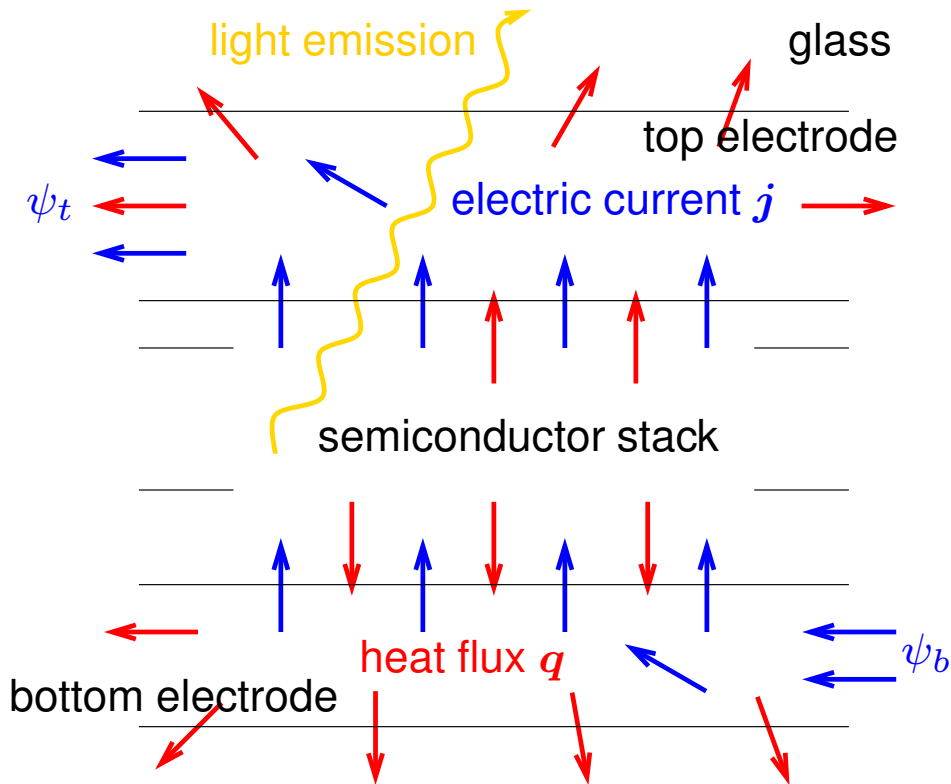
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- **heat transfer** governed by  
Fourier's law:  $q = -\lambda \nabla T$  [ $\text{Wm}^{-2}$ ]  
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temperature  $T$  [K]

# Charge transport and heat transfer

Multilayer semiconductor stack between two electrodes (e. g. OLED):



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temperature  $T$  [K]

- **electrical**  $\rightarrow$  **thermal** coupling via Joule heating  $\propto \sigma |\nabla \psi|^2$  [ $\text{Wm}^{-3}$ ].
- **thermal**  $\rightarrow$  **electrical** coupling via temperature-dependent charge transport properties, especially in the semiconductor stack.

# Dimensional reduction

Instead of using a full three-dimensional (3D) model for the charge transport and heat transfer in the semiconductor device we combine

- a two-dimensional (2D) model for each **thin-film** electrode with
- a zero-dimensional (0D) model for the semiconductor stack.

The **coupled 0D-2D approach** is important for reducing the computational cost since

- typical layers are very thin compared to their lateral dimensions (lateral  $\sim 10^{-3} \text{ m} \sim 10^{-2} \text{ m}$ , vertical  $\sim 10^{-8} \text{ m} \sim 10^{-6} \text{ m}$ ) and
- the smallest length scale in the computational domain usually determines the maximum mesh size in a discretization (stability).

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**3D:  $N$  vertical degrees of freedom (dofs)  $\rightsquigarrow \sim (10^5 N)^2$  lateral dofs**

**$\rightsquigarrow \sim 10^{10} N^3$  dofs in total!**

# Dimensional reduction in top electrode (1)

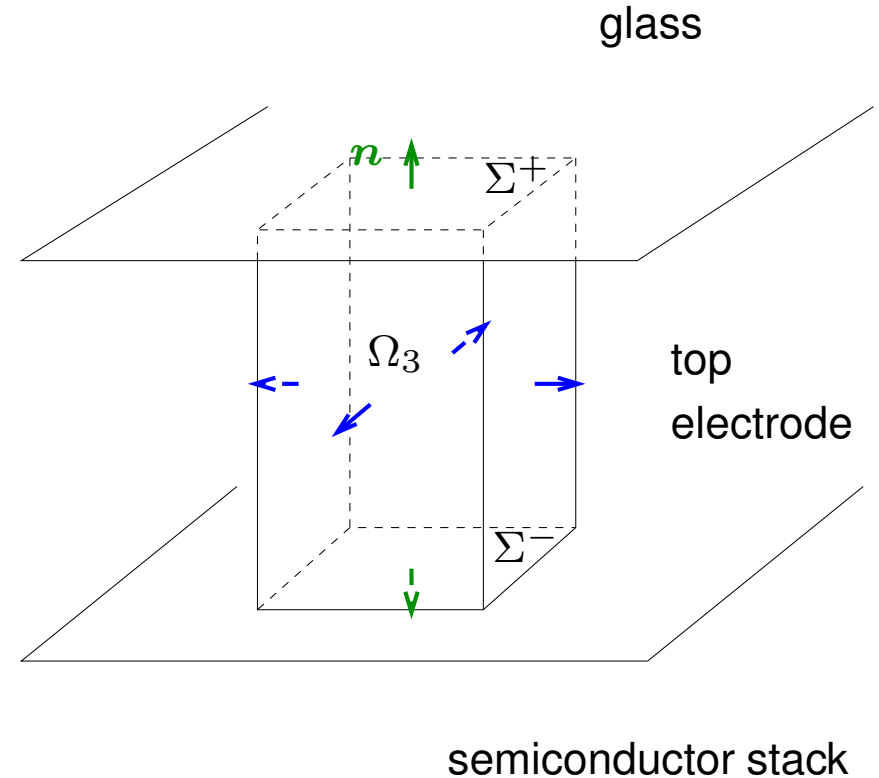
Special control volume with faces  $\Sigma^+$  and  $\Sigma^-$  at the top and bottom faces of the (top) electrode, where the outward electric current density is known. Steady-state equations:

$$\operatorname{div} \mathbf{j}_3 = 0 \quad \text{in } \Omega_3,$$

$$\mathbf{j}_3 \cdot \mathbf{n} = 0 \quad \text{on } \Sigma^+,$$

$$\mathbf{j}_3 \cdot \mathbf{n} = -j_s \quad \text{on } \Sigma^-.$$

$$\mathbf{j}_3(x, y, z) = \begin{pmatrix} j_{3,x}(x, y, z) \\ j_{3,y}(x, y, z) \\ j_{3,z}(x, y, z) \end{pmatrix}$$



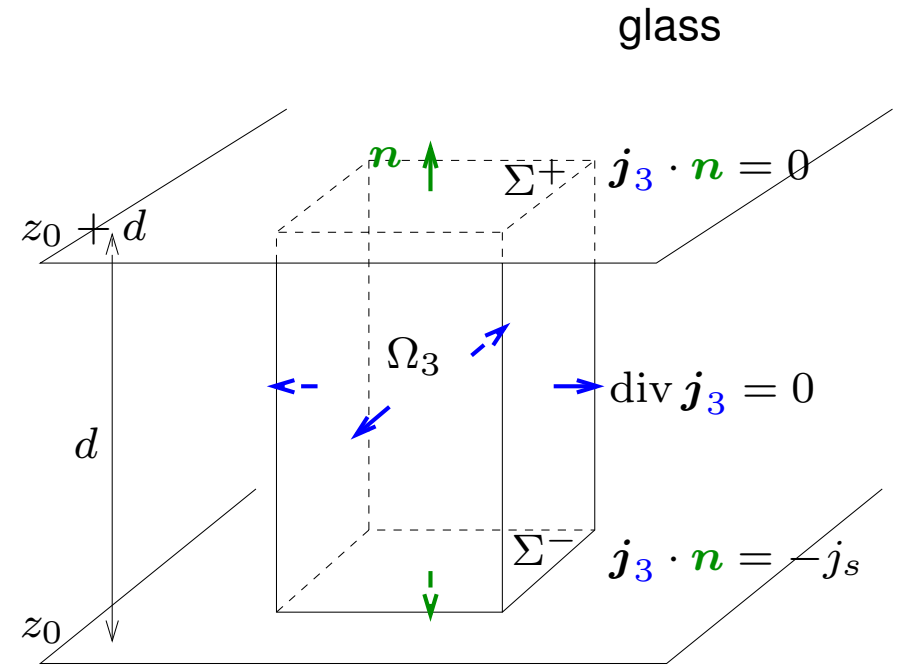
$j_s$ : current density [ $\text{Am}^{-2}$ ]  
out of the semiconductor stack into the top electrode, orthogonal to the interface.



# Dimensional reduction in top electrode (2)

$\text{div } \mathbf{j}_3 = 0$ , integrate in  $z$ -direction:

$$\begin{aligned}
 0 &= \int_{z_0}^{z_0+d} \text{div } \mathbf{j}_3 \, dz \\
 &= \int_{z_0}^{z_0+d} \frac{\partial j_{3,x}}{\partial x} + \frac{\partial j_{3,y}}{\partial y} + \frac{\partial j_{3,z}}{\partial z} \, dz \\
 &= \frac{\partial}{\partial x} \int_{z_0}^{z_0+d} j_{3,x} \, dz + \frac{\partial}{\partial y} \int_{z_0}^{z_0+d} j_{3,y} \, dz \\
 &\quad + \underbrace{j_{3,z}|_{z=z_0+d}}_{= \mathbf{j}_3 \cdot \mathbf{n}|_{\Sigma^+}} - \underbrace{j_{3,z}|_{z=z_0}}_{= (-\mathbf{j}_3 \cdot \mathbf{n})|_{\Sigma^-}} \\
 &= \text{div } \mathbf{j}_2 + 0 - j_s \Rightarrow \text{div } \mathbf{j}_2 = j_s
 \end{aligned}$$



lateral current density [ $\text{Am}^{-1}$ ]

$$\mathbf{j}_2(x, y) := \int_{z_0}^{z_0+d} \begin{pmatrix} j_{3,x}(x, y, z) \\ j_{3,y}(x, y, z) \end{pmatrix} dz.$$

# Dimensional reduction in top electrode (3)

Ohm's law  $\mathbf{j}_3 = \sigma \mathbf{E} = -\sigma \nabla \psi_3$  with the electrical conductivity  $\sigma$  [ $\text{Sm}^{-1}$ ] and with the **electric potential**  $\psi_3$  [V] (electric field  $\mathbf{E} = -\nabla \psi_3$  [ $\text{Vm}^{-1}$ ]).

Integration in the  $z$ -direction yields lateral current density  $\mathbf{j}_2(x, y) =$

$$\int_{z_0}^{z_0+d} \begin{pmatrix} j_{3,x}(x, y, z) \\ j_{3,y}(x, y, z) \end{pmatrix} dz = - \int_{z_0}^{z_0+d} \sigma(x, y, z) \begin{pmatrix} \frac{\partial \psi_3}{\partial x}(x, y, z) \\ \frac{\partial \psi_3}{\partial y}(x, y, z) \end{pmatrix} dz.$$

Assume  $\frac{\partial \sigma}{\partial z} \equiv 0$ , for  $z_0 < z < z_0 + d$ .

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$$\int_{z_0}^{z_0+d} \begin{pmatrix} j_{3,x}(x, y, z) \\ j_{3,y}(x, y, z) \end{pmatrix} dz = -\sigma(x, y) d \frac{1}{d} \int_{z_0}^{z_0+d} \begin{pmatrix} \frac{\partial \psi_3}{\partial x}(x, y, z) \\ \frac{\partial \psi_3}{\partial y}(x, y, z) \end{pmatrix} dz.$$

Assume  $\frac{\partial \sigma}{\partial z} \equiv 0$ , for  $z_0 < z < z_0 + d$ . Define the **averaged potential**

$$\psi_2(x, y) := \frac{1}{d} \int_{z_0}^{z_0+d} \psi_3(x, y, z) dz \quad [\text{V}]. \quad \text{Then } \mathbf{j}_2 = -R_{\square}^{\text{el}} \nabla \psi_2 \quad [\text{Am}^{-1}],$$

with the electrical **sheet resistance**  $R_{\square}^{\text{el}}(x, y) := (\sigma(x, y)d)^{-1}$  [ $\Omega/\square$ ]. The sheet resistance is negligible in thick layers ( $R_{\square}^{\text{el}} \rightarrow 0$  as  $d \rightarrow \infty$ ).

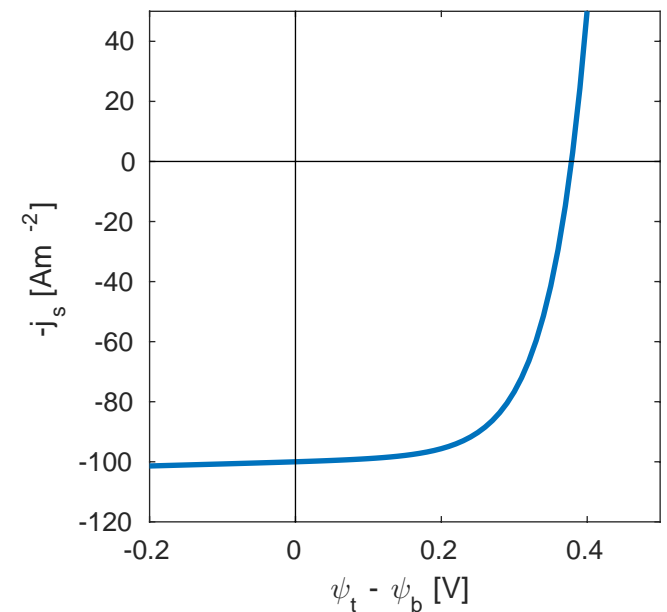
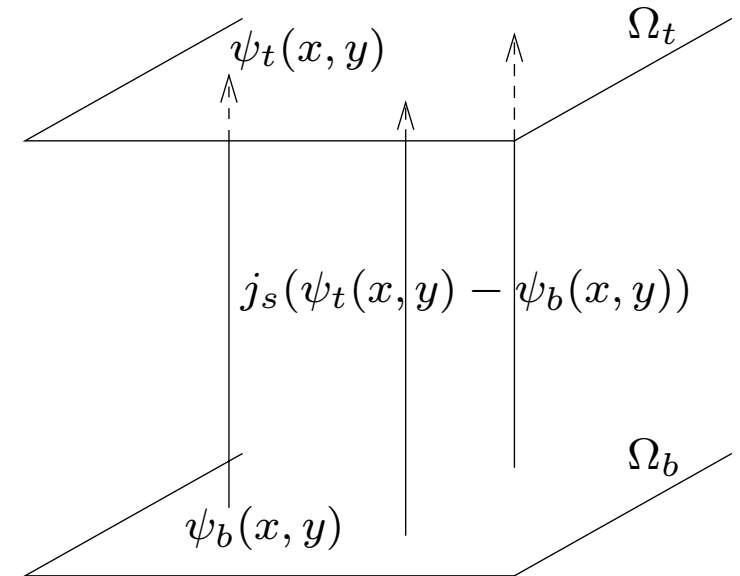
# Coupled 0D-2D electrical model

**2D:** Combine charge balance and constitutive equations in the top electrode. Use the same procedure in the bottom electrode to obtain the system of PDEs

$$- \operatorname{div}(R_{\square,t}^{\text{el}}{}^{-1} \nabla \psi_t) = j_s \quad \text{in } \Omega_t,$$

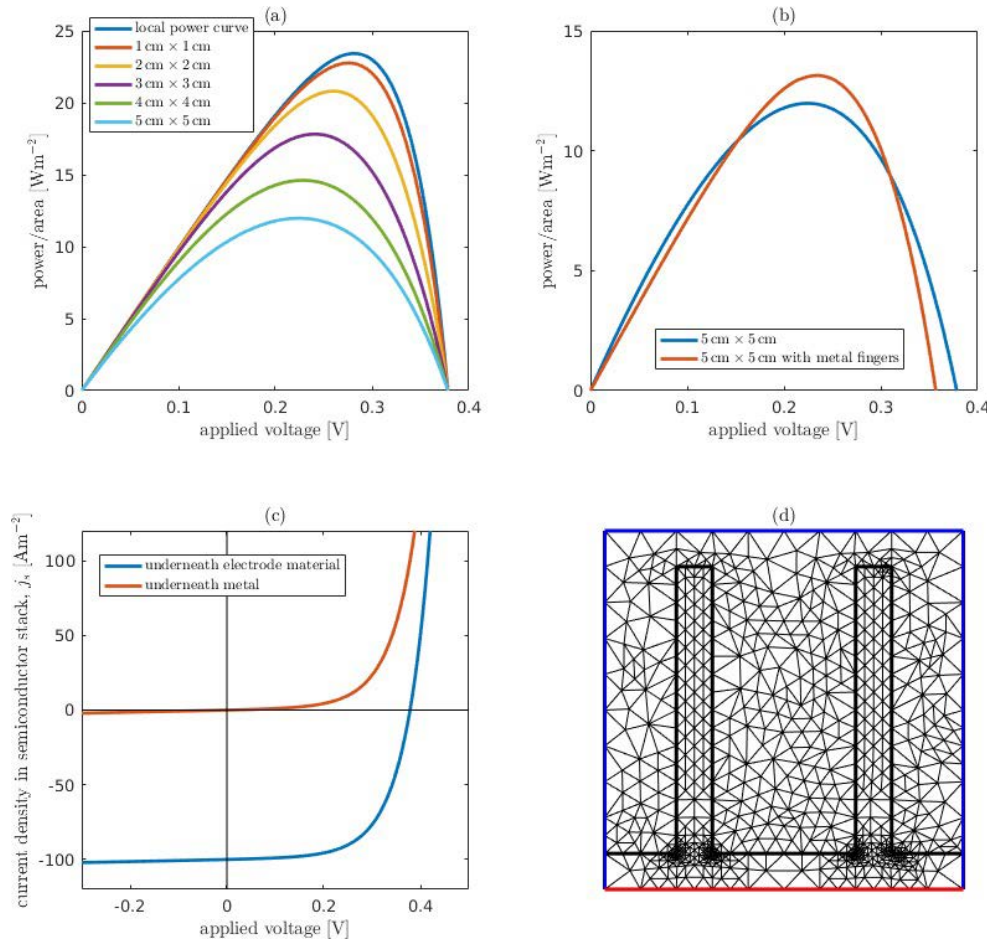
$$- \operatorname{div}(R_{\square,b}^{\text{el}}{}^{-1} \nabla \psi_b) = -j_s \quad \text{in } \Omega_b.$$

**0D:** In the semiconductor stack we assume no lateral current, such that the (vertical) current in the stack is determined by the potential difference between the electrodes:  $j_s = j_s(\psi_t - \psi_b)$ .

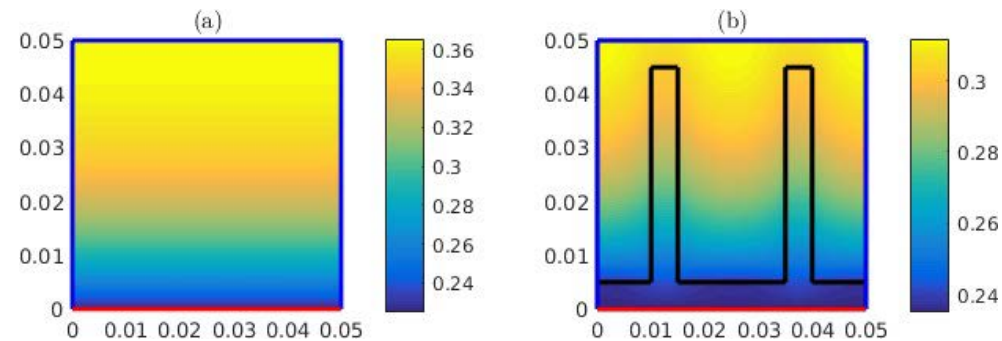


# Large-area electrical solar-cell model: results

Discretization of PDEs using the **finite element method (FEM)**, together with standard techniques such as adaptive mesh refinement.



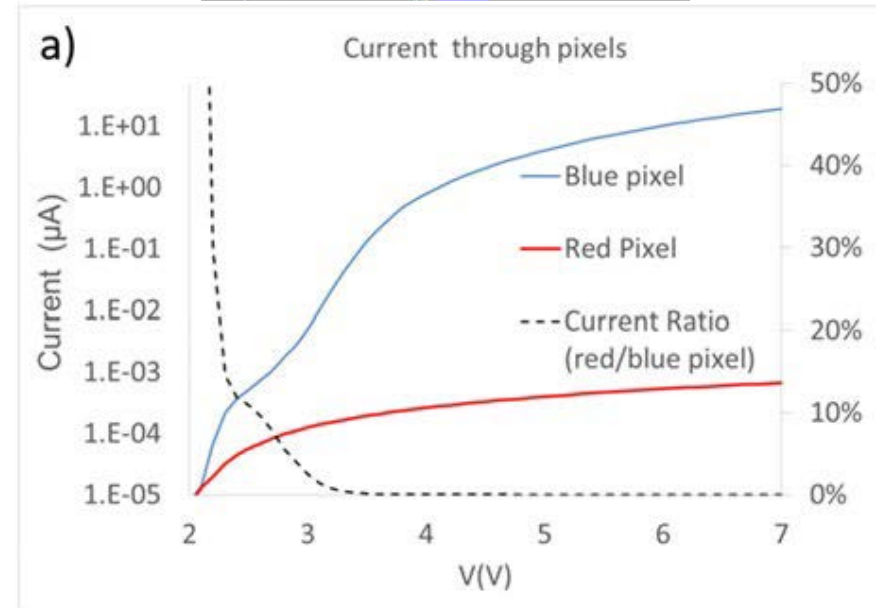
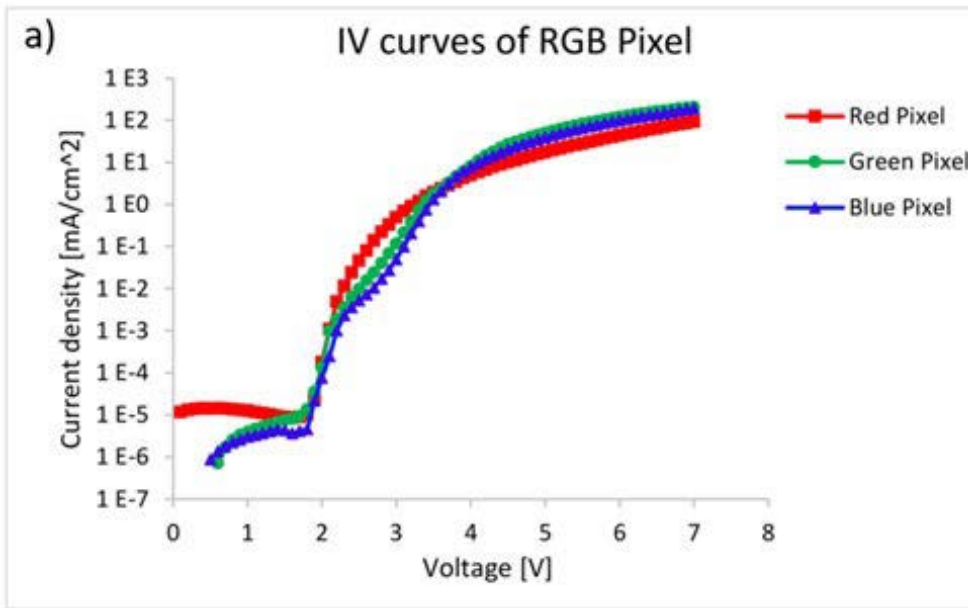
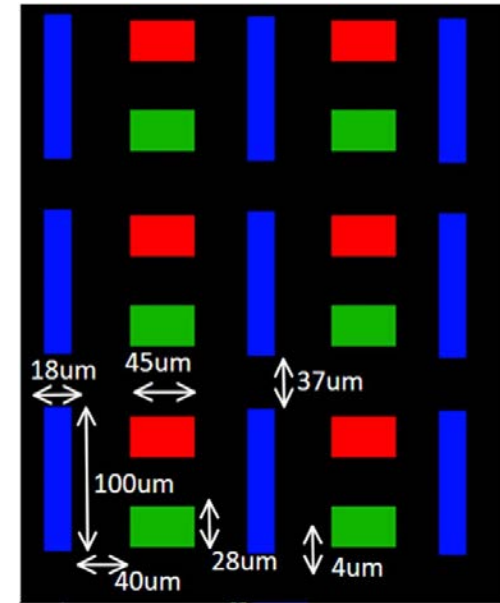
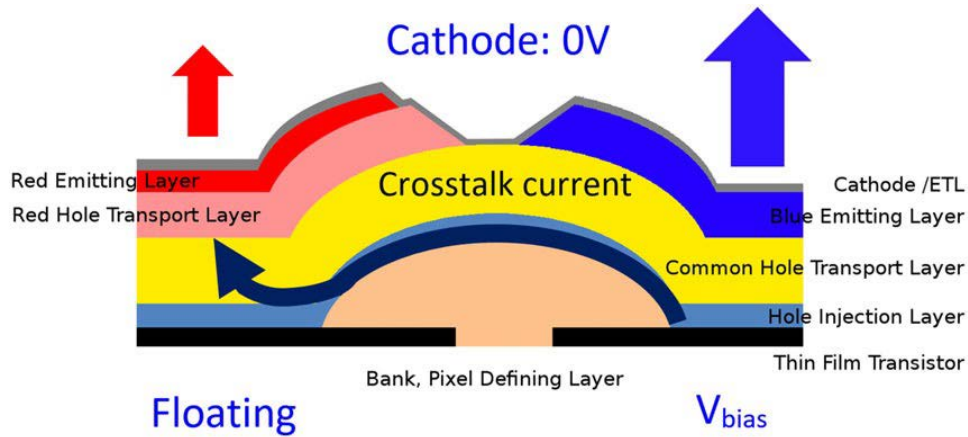
electric potential [V] at MPP:



Due to the electrical sheet resistance the maximum power increases sublinearly with the device area.

CK et al., Int. J. Multiphys. 11 (2), 2017

# Large-area electrical OLED model: crosstalk



Diethelm et al., J. Inf. Disp. 19 (2), 2018; Penninck et al., J. Soc. Inf. Disp., 2018

# 0D-2D electrothermal model

Dimensional reduction of the thermal energy balance in the top and bottom electrodes in a similar way as before, together with Fourier's law, leads to

$$-\operatorname{div}\left(R_{\square,t}^{\text{el}}{}^{-1}\nabla\psi_t\right) = f_t^{\text{el}}(\psi_t, T_t, \psi_b, T_b),$$

$$-\operatorname{div}\left(R_{\square,t}^{\text{th}}{}^{-1}\nabla T_t\right) = f_t^{\text{th}}(\psi_t, T_t, \psi_b, T_b),$$

$$-\operatorname{div}\left(R_{\square,b}^{\text{el}}{}^{-1}\nabla\psi_b\right) = f_b^{\text{el}}(\psi_t, T_t, \psi_b, T_b),$$

$$-\operatorname{div}\left(R_{\square,b}^{\text{th}}{}^{-1}\nabla T_b\right) = f_b^{\text{th}}(\psi_t, T_t, \psi_b, T_b),$$

with the thermal sheet resistances

$$R_{\square}^{\text{th}}(x, y) := (\lambda(x, y)d)^{-1} [\text{KW}^{-1}/\square].$$

- **Electrical** → **thermal**:

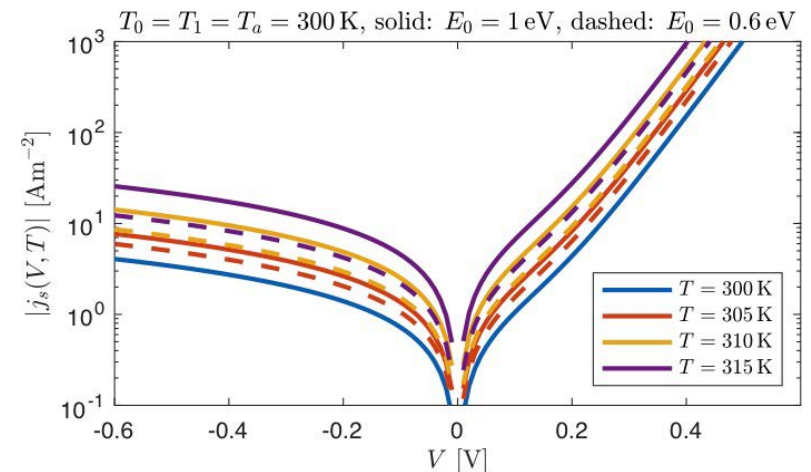
- Joule heating in the electrodes,  $R_{\square}^{\text{el}}{}^{-1}|\nabla\psi|^2$ ,

- Joule heating in the semiconductor stack

$$\propto (1 - \eta)|Vj_s(V)|,$$

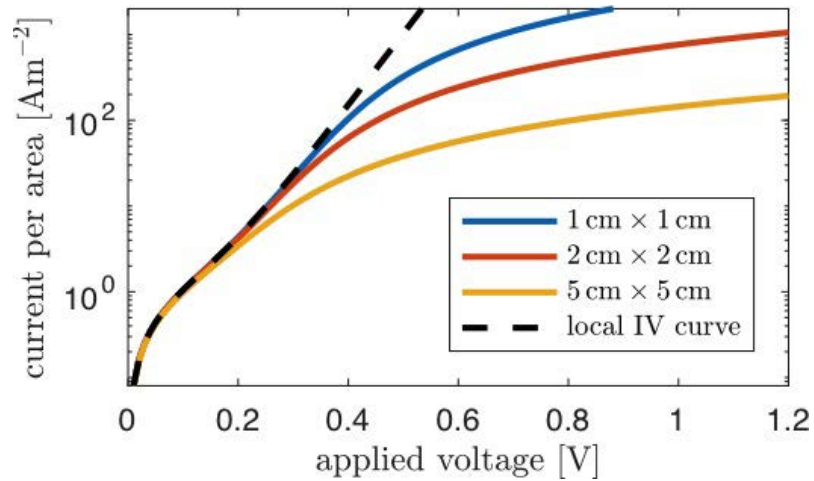
$$V := \psi_t - \psi_b.$$

- **Thermal** → **electrical**:

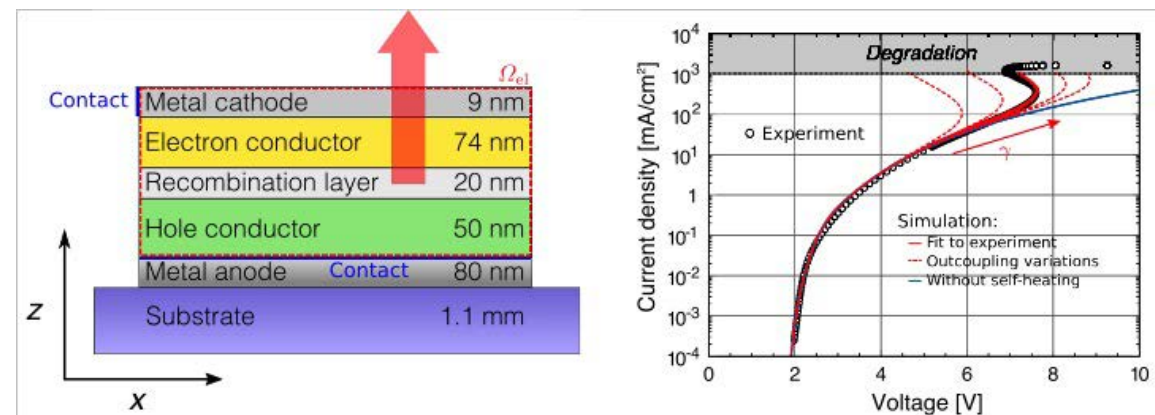
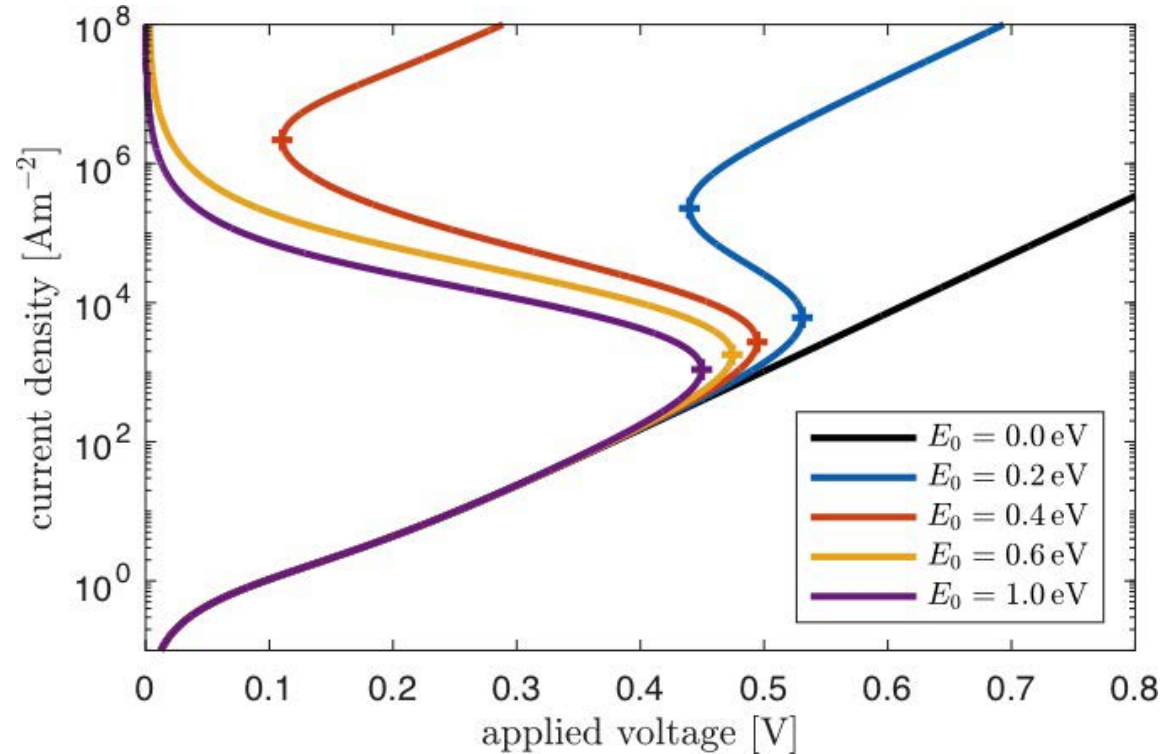


# IV curves with negative differential resistance

For a plain OLED device the electric current decreases with increasing device area (sheet resistance):



Together with thermal → electrical coupling we obtain S-shaped device-IV curves.



Liero et al., Opt Quant Electron, 2017



# Conclusions and outlook

- We presented a **coupled 0D-2D electrothermal model** for the **simulation of large-area semiconductor devices**.
- Several experimental findings could be qualitatively **reproduced**.
- Simulation studies may help to explore **new device-design ideas**.

Some possible extensions:

- From steady-state model to **transient** and to **AC** models.
- **More complex mathematical models for the semiconductor stack**, p. ex. using a drift-diffusion model ( $\rightsquigarrow$  coupled 1D-2D model).

Possible mathematical topic:

- Analytical/numerical investigation of the **model-reduction error (3D  $\rightarrow$  0D-2D)**, depending on electrode thickness.